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Notice of Allowability	Application No.	Applicant(s)
	09/457,743	SAKURAI ET AL.
	Examiner	Art Unit
	Monique R Jackson	1773
The MAILING DATE of this communication appe All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this ap or other appropriate communication IGHTS. This application is subject to	plication. If not included  n will be mailed in due course. THIS
1. X This communication is responsive to the Amendment filed	<u>6/7/04</u> .	
2. ⊠ The allowed claim(s) is/are <u>1,4-6 and 18</u> .		
3. $igotimes$ The drawings filed on <u>28 February 2003</u> are accepted by the	ne Examiner.	
4.		
Attachment(s)  1. Notice of References Cited (PTO-892)  2. Notice of Draftperson's Patent Drawing Review (PTO-948)  3. Information Disclosure Statements (PTO-1449 or PTO/SB/0)  Paper No./Mail Date	6. ☐ Interview Summary Paper No./Mail Dat	te
4. Examiner's Comment Regarding Requirement for Deposit of Biological Material	8. ⊠ Examiner's Stateme 9. □ Other	ent of Reasons for Allowance

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1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows:

The claim identifier for Claim 6 has been changed from "(Currently Presented)" to "(Currently Amended)" in accordance with current amendment requirements.

2. The following is an examiner's statement of reasons for allowance: the closest prior art, Konishi et al (USPN 5,891,531), teaches a thin fluoride film on a substrate and a process for producing the thin film of fluoride on a substrate wherein the process comprises reacting a gaseous fluorinating agent such as NF<sub>3</sub>, SF<sub>6</sub> and CF<sub>4</sub>, and gas of volatile organometallic compound, wherein it is preferred that barium is comprised in the composition of the thin film of the fluoride by using a volatile organobarium compound in which at least one organic molecule having 3 to 12 heteroatoms which can coordinate to one barium ion is coordinated as one of the volatile organometallic compounds with examples of the heteroatom including oxygen, nitrogen and sulfur. However, Konishi et al do not teach or suggest that the fluoride layer is represented by the formula MO<sub>x</sub>F<sub>y</sub> as instantly claimed.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

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Any inquiry concerning this communication or earlier communications from the examiner should be directed to Monique R Jackson whose telephone number is 571-272-1508. The examiner can normally be reached on Mondays-Thursdays, 8:00AM-4:30PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Paul J Thibodeau can be reached on 571-272-1516. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

MONIQUE R. JACKSON

Monique R. Jackson

Primary Examiner

Technology Center 1700

July 21, 2004